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Vacuum and Process Control Publications

1. **The Journal of Vacuum Science & Technology A**. Vacuum, Surfaces and Films. Published six times annually by the American Vacuum Society (www.vacuum.org). A consistently good refereed journal with lots of papers on vacuum technology subjects. Available on-line: http://ojps.aip.org/jvsta/.

2. **The Journal of Vacuum Science & Technology B**. Microelectronics and Nanometer Structures. Published six times annually by the American Vacuum Society (www.vacuum.org). A consistently good journal with lots of refereed papers on semiconductor processing issues. Available on-line: http://ojps.aip.org/jvstb/

3. **Vacuum**. The international journal Vacuum publishes high quality papers on latest advances in the many areas which now require the production and control of a

working environment at pressure below one atmosphere. Published by Pergamon Press, a division of Elsevier Books and Journals: www.elsevier.nl.

4. **Review of Scientific Instruments**. A monthly journal from the American Institute of Physics (www.aip.org) devoted to scientific instruments, apparatus and techniques. Available on-line: http://ojps.aip.org/rsio/. Always a very fun journal to read. A must-read for instrument designers and experimental scientists trying to stay up-to-date.

5. **R&D Magazine**. A monthly Cahners publication devoted to general research and development issues. Available on the web: www.rdmag.com

6. **Vacuum&ThinFilm**. A monthly publication by the HIS Publishing Group (Libertyville, IL, Ph. 847-362-8711). Loaded with useful information on vacuum and semiconductor processing issues. Particularly good are all the articles by Phil Danielson, who reminds us of the fundamentals of vacuum technology in each issue. Unfortunately this publication went out of circulation with its last issue of 1999.

7. **Vacuum Technology &Coating**. A new magazine that started on JAN 2000. For subscriptions contact www.vactechmag.com. Loaded with vacuum information.

8. **Semiconductor International**. Another monthly Cahners publication dedicated to semiconductor processing subjects. Available on the web: www.semiconductor.net

9. **Solid State Technology**. A monthly PennWell publication, available on-line: www.solid-state.com

10. **Micro**. A monthly Cannon Communications Publication that often deals with vacuum contamination issues. Available on-line: www.micromagazine.com.. They have a deep article archive in their website where you can find most of the MICRO papers referenced here.

11. **FUTURE FAB International**. Published by Technology Publishing, Ltd. in the U. K., e-mail: tech@techpub.org.

12. **AVS Monograph Series**. The American Vacuum Society (AVS, www.vacuum.org) publishes a whole series of monographs on vacuum technology and processing subjects. They are all very good and worth checking out. Some of the books are required minimum reading for vacuum practtioners.

Vacuum and Process Control Websites

1. www.vacuumlab.com: An on-line "Journal of Useful and Practical Vacuum Technology", published on-line by Phil Danielson. No advertisements, no product selling, just plain old vacuum knowledge. We highly recommend it. It even includes an "Ask Phil" section where you can submit any of those vacuum questions that

have puzzled you in the past. We encourage you to challenge Phil! At this point the website is completely free and open to the general public.

2. www.thinkSRS.com: The SRS website is packed with very useful application notes related to vacuum applications and instrumentation. Check it out! We are constantly adding to our list of applications.

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